Application No.	Applicant(s)		
10/675,203	BUCHAN ET AL.		
Examiner	'Art Unit		
Patricia A. George	1765		
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<u>//27/2006</u> .			
e been received. e been received in Application	No	tion from the	
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nitted. Note the attached EXAN ves reason(s) why the oath or d	MNER'S AMENDMENT or N leclaration is deficient.	OTICE OF	
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.			
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached			
1)  hereto or 2)  to Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).			
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.			
6. ☐ Interview Sun Paper No./M 7. ☐ Examiner's A	nmary (PTO-413), lail Date mendment/Comment tatement of Reasons for Allo	owance VINH EXAMINER	
	Examiner  Patricia A. George  ears on the cover sheet with (OR REMAINS) CLOSED in to or other appropriate communities. This application is sufficient of the second of the	BUCHAN ET AL.	

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## **DETAILED ACTION**

## Response to Amendment

The amendments filed on 10-/27/2006 are sufficient to overcome the prior art rejection, filed 7/27/2006.

## Allowance

Claim 1-4, 6-14, and 16-20 allowed. The following is an examiner's statement of reasons for allowance: Prior art does not suggest or disclose a method for fabricating recording head sliders made from silicon substrate with SiO2 overcoats which include all of applicants defined steps, resulting in a structure of a primary patterned RIE mask, over a pattern SiO2 overcoat layer, and a Al2O3 DRIE secondary mask, utilizing both RIE and DRIE methods of etching. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Patricia A. George whose telephone number is (571)272-5955. The examiner can normally be reached on weekdays between 7:00am and 4:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on (571)272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Patricia A George Examiner

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12/21/2006